

Search History:

Limited Classification Search

The Patent Analyst performed a limited classification search within the following US, IPC, CPC, ECLA, or F-Term classification areas:

CPC Class/Subclass(es): G02B 26/005; G02B 26/00; G09G 3/348; H01L 21/00; H01L 21/027; H01L 27/00 (2020.02)

IPC (8) Class/Subclass(es): G02B 26/00; H01L 21/027; H01L 21/00; H01L 27/00 (2020.01)

U.S. Class/Subclass(es): 438/71; 438/149; 438/164

See Global Search Results.

Global Patent Literature Text Search

The Patent Analyst performed the following global text search, which was not limited by classification but may or may not have been limited by other criteria:

Questel Orbit: <https://www.orbit.com>

#	Search query	Results
1	((CORNING 2D INCORPORATED)/PA/OPA)	392
2	((WYNNE 2D THOMAS)/IN/OIN/INH/INV)	39
3	1 AND 2	0
4	1 OR 2	431
5	4 AND (PATTERN+ S INSULATING S LAYER+)/TX	2
6	4 AND (ELECTROWET+)/TX	2
7	(ELECTROWET+ AND (INSULAT+ S ABLAT+) AND (CONDUCT+ 3D MASK))/TX	30
8	(H01L-021/027)/CPC	15667
9	(H01L-021/027)/IPC	122533
10	8 OR 9	124679
11	10 AND (CONDUCT+ S LAYER+ S MASK+)/TX	7456
12	10 AND (INSULAT+ S LAYER+ S ABLAT+)/TX	56
13	11 AND 12	24
14	(G02B-026/005)/CPC	1366
15	(G02B-026/00)/IPC	11677
16	(G02B-026/00)/CPC	5552
17	8 OR 9 OR 14 OR 15 OR 16	138003
18	17 AND (ELECTROWET+/TI/AB)	792

19	(G09G-003/348)/CPC	296
20	(H01L-027/00)/CPC	1580
21	(H01L-027/00)/IPC	12865
22	(H01L-021/00)/IPC	76300
23	(H01L-021/00)/CPC	9158
24	19 OR 20 OR 21 OR 22 OR 23	89110
25	24 AND (INSULAT+ S LAYER+ S ABLAT+)/TX	250
26	24 AND (CONDUCT+ S LAYER+ S MASK+)/TX	8881
27	25 OR 26	9036
28	25 AND 26	95
29	24 AND (ELECTROWETT+ AND (INSULAT+ S LAYER+ S ABLAT+))/TX	3
30	24 AND (ELECTROWETT+ AND (CONDUCT+ S LAYER+ S MASK+))/TX	35
31	24 AND (ELECTROWETT+ AND (CONDUCT+ S LAYER+ S MASK+) AND WELLS)/TX	7
32	17 AND (ELECTROWETT+ AND (CONDUCT+ S LAYER+ S MASK+) AND WELLS)/TX	4
33	10 AND (ELECTROWETT+ AND (CONDUCT+ S LAYER+ S MASK+) AND WELLS)/TX	2
34	438071/PCL	575
35	438164/PCL	820
36	438149/PCL	2861
37	34 OR 35 OR 36	4031
38	37 AND (ELECTROWETT+ AND (CONDUCT+ S LAYER+ S MASK+))/TX	4
39	37 AND (ELECTROWETT+ AND (CONDUCT+ AND INSULAT+ AND MASK+))/TX	8
40	37 AND (INSULAT+ S LAYER+ S ABLAT+)/TX	39
41	24 AND (INSULAT+ S LAYER+ S ABLAT+)/TX	250

Google Patents: <https://patents.google.com>

#	Search query	Results
1	METHODS FOR FORMING PATTERNED INSULATING LAYERS ON CONDUCTIVE LAYERS AND DEVICES MANUFACTURED USING SUCH METHODS	100+
2	patterning insulator layer laser ablation annular patterns	100+
3	patterning insulator layer over conductive layer	100+
4	patterning insulator layer laser ablation over mask on conductive layer	100+

5	removing an annular region of an insulating layer overlying a perimeter of an opening in a mask	100+
6	removing insulator region over mask opening on conductive layer	100+
7	electrowetting devices insulating layer over conductive layer	100+
8	electrowetting devices insulating layer over conductive layer mask ring pattern	100+
9	electrowetting devices conducting layer on wafer mask to form wells	100+
10	conducting layer on wafer mask to form wells	100+
11	conducting layer on wafer mask to form wells insulating layer ring shaped holes	100+
12	conducting layer on wafer mask to form wells insulating layer annular holes	100+

Computer Accessed Text Databases Searched

The Patent Analyst searched the following computer accessed text databases:

Google Scholar: <https://scholar.google.com/>

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1	METHODS FOR FORMING PATTERNED INSULATING LAYERS ON CONDUCTIVE LAYERS AND DEVICES MANUFACTURED USING SUCH METHODS	100+
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3	patterning insulator layer over conductive layer	100+
4	patterning insulator layer laser ablation over mask on conductive layer	100+
5	removing an annular region of an insulating layer overlying a perimeter of an opening in a mask	100+
6	removing insulator region over mask opening on conductive layer	100+
7	electrowetting devices insulating layer over conductive layer	100+
9	electrowetting devices insulating layer over conductive layer mask ring pattern	100+
9	electrowetting devices conducting layer on wafer mask to form wells	100+
10	conducting layer on wafer mask to form wells	100+
11	conducting layer on wafer mask to form wells insulating layer ring shaped holes	100+
12	conducting layer on wafer mask to form wells insulating layer annular holes	100+

Date search was completed: 12 February 2020

SV/CC